

## **TEST PATTERN, INSPECTION METHOD, AND DEVICE MANUFACTURING METHOD**

### **ABSTRACT OF THE DISCLOSURE**

In a method according to one embodiment of the invention, aberrations  
5 in a lithographic apparatus are detected by printing a test pattern having at  
least one degree of symmetry and being sensitive to a particular aberration in  
the apparatus, and using a scatterometer to derive information concerning the  
aberration. The test structure may comprise a two-bar grating, in which case  
the inner and outer duty ratios can be reconstructed to derive information  
10 indicative of comatic aberration. Alternatively, a hexagonal array of dots can  
be used, such that scatterometry data can be used to reconstruct dot diameters  
indicative of 3-wave aberration.